

<https://www.spst-photopolymer.org>

Call for Papers

ICPST-39

The 39th International Conference
of
Photopolymer Science
and
Technology

Materials & Processes
for
Advanced Lithography,
Nanotechnology and Phototechnology

June 27 - 30, 2022

**International Conference Hall
Makuhari Messe, Chiba, Japan
or
On-line Meeting**

**Sponsored by the Society of Photopolymer
Science and Technology (SPST)**

In Cooperation with
The Technical Association of
Photopolymers, Japan
The Chemical Society of Japan
The Society of Polymer Science, Japan
Endorsed by
The Japan Society of Applied Physics
(Tentative)

Introduction

The 39th International Conference of Photopolymer Science and Technology, Materials & Processes for Advanced Lithography, Nanotechnology and Phototechnology (**ICPST-39**) organized by SPST will **be held online live meeting** in the period of June 27 – 30, 2022 because of the COVID-19 pandemic.

All the contributors of papers on the scientific progress and the technical development of photopolymers are cordially invited.

Conference URL to participate will be sent to the registered email address individually after the registration and payment are completed.

Scopes

The conference covers a wide range of topics relevant to photopolymer science and technology in the following fields:

A. English Symposia

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
- A6. Nanoimprint
- A7. 193 nm Lithography Extension and EUV HVM Readiness
- A8. Photopolymers in 3-D Printing/ Additive Manufacturing
- A9. 2D and Stimuli Responsive Materials for Electronics & Photonics
- A10. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices
- A11. Chemistry for Advanced Photopolymer Science
- A12. Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices
- A13. Fundamentals and Applications of Biomimetics Materials and Processes
- A14. General Scopes of Photopolymer Science and Technology
- P. Panel Symposium "Beyond Sub-10 nm Lithography -From a Material Design and Development Perspective-"

B. Japanese Symposia

- B1. Polyimides and High Thermally Stable Resins
-Functionalization and Practical Applications-
- B2. Plasma Photochemistry and Functionalization of Polymer Surfaces
- B3. General Scopes of Photopolymer Science and Technology

Language and Oral Presentation Time

English is used for presentations in English Symposia and Panel Symposium. Japanese and English are used for presentations in Japanese Symposia. Each presentation will not be longer than 20 minutes including discussion except for the notified lectures.

Application to Scientific Program

Apply to [Conference → Presentation-Info Submission] at the SPST Homepage (<https://www.spst-photopolymer.org/>) before **February 14, 2022**.

Editorial Office

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Papers

Papers submitted to ICPST-39 are published in Journal of Photopolymer Science and Technology, Vol. 35 (2022) after reviewing on the Journal's standard. Journal will be distributed to each participant during the conference. Preparation of manuscripts for the Journal should be followed to "Instructions to Authors" and "Manual for Manuscript Writing". Refer "Page Layout Sample" and use "Sample Manuscript (Manuscript Template)". Submit the manuscripts to [Journal → Submission & Reviewing of MS] at the SPST Homepage before **April 1, 2022**. The Journal will be published and mailed before ICPST-39.

Registration for Participants

All the participants including speakers are requested to register in [Conference → Registration] at the SPST Homepage before **June 26, 2022**.

Registration fee of whole conference is ¥35,000 yen for participants including all the speakers

Registration fee of whole conference is ¥10,000 yen for students.

Conference Office

The 39th International Conference of Photopolymer Science and Technology (ICPST-39)

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<https://www.spst-photopolymer.org>

講演募集

ICPST-39

第39回
国際フォトポリマーコンファレンス

リソグラフィ、ナノテクノロジー、
フォトテクノロジー
-材料とプロセスの最前線-

2022年6月27日(月)～30日(木)

幕張メッセ国際会議場
または
オンライン開催

主催 フォトポリマー学会 (SPST)

協賛 (交渉中) フォトポリマー懇話会、
日本化学会、高分子学会
後援 (交渉中) 応用物理学会

第39回国際フォトポリマーコンファレンスを下記の要領で開催いたします。 フォトポリマーに関心をお持ちの方々は是非、御参加下さい。

日 時 2022年6月27日(月)～30日(木)

会 場 ZOOMによるオンライン(ライブ)
詳細は参加申込者に個別に案内致します。

講演内容

フォトポリマーに関する科学と技術の研究報告

A. 英語シンポジウム

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
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- A13. Fundamentals and Applications of Biomimetics Materials and Processes
- A14. General Scopes of Photopolymer Science and Technology
- P. Panel Symposium "Beyond Sub-10 nm Lithography -From a Material Design and Development Perspective-

B. 日本語シンポジウム

- B1. ポリイミド及び高温耐熱樹脂-機能化と応用
- B2. プラズマ光化学と高分子表面機能化
- B3. 一般講演：(1) 光物質化学の基礎(光物理過程、光化学反応など)、(2)光機能素子材料(分子メモリー、情報記録材料、液晶など)、(3)光・レーザー電子線を活用する合成・重合・パターンニング、(4)フォトファブ리케이션(光成型プロセス、リソグラフィ)、(5)レジスト除去、エッチング、洗浄、(6)装置(光源、照射装置、計測、プロセスなど)

講演時間と言語

原則として討論時間を含め20分。英語シンポジウムは英語、日本語シンポジウムは日本語及び英語

講演申込

学会ホームページ (<https://www.spst-photopolymer.org/>) [講演募集ICPST-39→日本語会場発表申し込み]から申し込んでください。

申込締切 2022年2月14日(月)

論文の出版

ICPST-39の論文はJournal of Photopolymer Science and Technology Vol. 35 (2022) にJournal基準による審査を経て出版されます。論文原稿は、完全原稿を作成し、2022年4月1日(金)までに学会ホームページ(<https://www.spst-photopolymer.org/>)の [Journal→ Submission&Reviewing of MS] に投稿してください。

フォトポリマー学会出版局

〒078-8510 北海道旭川市緑が丘東2条1丁目1-1
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E-mail: mayama@asahikawa-med.ac.jp

参加申込予約締切 2022年6月26日(日)

参加登録方法

講演者を含む全参加者はフォトポリマー学会のホームページ(<https://www.spst-photopolymer.org/>講演募集icpst-39-2022/参加登録/)より登録ください。なお、お支払いはクレジットカード払いのみになります。
一般参加費 35,000円
学生参加費 10,000円

展示会

コンファレンス期間中展示会を併設します。展示会出展企業を募集いたします。事務局に申し込みまたはお問い合わせ下さい。

第39回 国際フォトポリマーコンファレンス事務局

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